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Journal Information

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Classification History

Year	A+	A	B	C
2026				
2025				
2024				
2023				
2021/2022			✓	
2020			✓	
2019		✓		
2018		✓		

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Recent Articles

Preface
2009-11-1 Vol. 27 Issue 6 Pages 2502-2502
Authors: Elizabeth Dobisz
DOI: 10.1116/1.3269923

Direct e-beam writing of 1nm thin carbon nanoribbons
2009-11-1 Vol. 27 Issue 6 Pages 3059-3062
Authors: C. T. Nottbohm, A. Turchanin, A. Beyer et al.
DOI: 10.1116/1.3253536

Pushing extreme ultraviolet lithography development beyond 22 nm half pitch
2009-11-1 Vol. 27 Issue 6 Pages 2911-2915
Authors: Patrick P. Naulleau, Christopher N. Anderson, Lorie-Mae Baclea-an et al.
DOI: 10.1116/1.3237092

Fabrication of nanodot array molds by using an inorganic electron-beam resist and a postexposure bake
2009-11-1 Vol. 27 Issue 6 Pages 2832-2836
Authors: Tetsuro Manabe, Jun Taniguchi, Kiyoshi Ishikawa
DOI: 10.1116/1.3253649

Evaluation of each electron beam and exposure results with four column cells in multicolumn e-beam exposure system
2009-11-1 Vol. 27 Issue 6 Pages 2518-2523
Authors: Akio Yamada, Hiroshi Yasuda, Masaki Yamabe
DOI: 10.1116/1.3253614

Application of neural network to controlling three-dimensional electron-beam exposure distribution in resist
2009-11-1 Vol. 27 Issue 6 Pages 2572-2579
Authors: C. Guo, S.-Y. Lee, S. H. Lee et al.
DOI: 10.1116/1.3259959

Development and characterization of an iodine field emission ion source for focused ion beam applications
2009-11-1 Vol. 27 Issue 6 Pages 2648-2653
Authors: Timothy P. Fedkiw, Paulo C. Lozano
DOI: 10.1116/1.3253604

Near neighbor averaging: A technique for improving image uniformity in aperture array lithography
2009-11-1 Vol. 27 Issue 6 Pages 2674-2678
Authors: A. Nasrullah, D. Smith, T. Sherlock et al.
DOI: 10.1116/1.3265462

Self-aligned fabrication of 10 nm wide asymmetric trenches for Si/SiGe heterojunction tunneling field effect transistors using nanoimprint lithography, shadow evaporation, and etching
2009-11-1 Vol. 27 Issue 6 Pages 2790-2794
Authors: Chao Wang, Stephen Y. Chou
DOI: 10.1116/1.3237138

Evaluation of nanoimprint lithography as a fabrication process of phase-shifted diffraction gratings of distributed feedback laser diodes
2009-11-1 Vol. 27 Issue 6 Pages 2776-2780
Authors: Masaki Yanagisawa, Yukihiro Tsuji, Hiroyuki Yoshinaga et al.
DOI: 10.1116/1.3244631